



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

M. Saldana

Application No: 10/789,486

Filed: February 26, 2004

For: METHODS WITH RESOLUTION
ENHANCEMENT FEATURE FOR IMPROVING
ACCURACY OF CONVERSION OF REQUIRED
CHEMICAL MECHANICAL POLISHING PRESSURE
TO FORCE TO BE APPLIED BY POLISHING HEAD
TO WAFER

Group: 2125

Examiner: Kasenge, C.

Docket No: LAM2P255D1

Date: April 19, 2005

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on April 19, 2005.

Signed: _____

Kay Harlow

COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

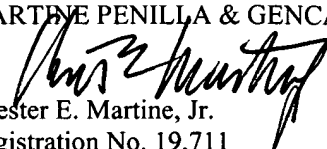
Commissioner for Patents
Alexandria, VA 22313-1450

Sir:

This is a response to the Statement of Reasons For Allowance mailed 2/7/05. Reference is made to the sentence in the Statement that includes "The allowability, at least in part, resides in the fact that neither reference teaches an apparatus...". Applicant notes that the allowed claims define various methods. Thus, it is respectfully requested that this sentence be revised to read as follows:

"The allowability, at least in part, resides in the fact that neither reference teaches a method comprising the operations of dividing the pressure range by the value of a component resolution to define scale portions of the pressure range, generating a first output signal to identify one of the scale portions that includes the desired value, and generating a second output signal to identify a set point that defines the requested value in the identified scale portion."

Respectfully submitted,
MARTINE PENILLA & GENCARELLA, LLP


Chester E. Martine, Jr.
Registration No. 19,711

710 Lakeway Drive, Suite 200
Sunnyvale, CA 94085
Telephone: (408) 749-6900
Customer Number 25920